

ABSTRACT

There is provided a photosensitive composition which possesses excellent storage stability and can yield an interlayer insulation film with an improved film thickness limit. The photosensitive composition is characterized by comprising: a modified polysilsesquiazane having a weight average molecular weight of 500 to 200,000 comprising basic constitutional units represented by formula $-\text{SiR}^1(\text{NR}^2)_{1.5}-$ wherein R^1 's each independently represent an alkyl group having 1 to 3 carbon atoms or a substituted or unsubstituted phenyl group; R^2 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group, up to 50% by mole of the basic constitutional units having been replaced by a linking group other than the silazane bond; and a photoacid generating agent.